

ABSTRACT

The present application relates to a wafer cleaning apparatus. The wafer cleaning apparatus comprises a first cleaning tank, a second cleaning tank, a storage tank, a first heater, and a controller. Besides, the wafer cleaning apparatus stores SPM solution discharged from the second cleaning tank via the storage tank, and controls the storage tank via the controller to transfer the SPM solution heated to a preset temperature range by the first heater into the first cleaning tank when the first cleaning tank performs the SPM solution replacement. Through the above method, the problem that a wet-batch SPM cleaning equipment or a cleaning equipment for combined wet-batch and single-wafer cleaning has reached the limit of further SPM solution savings is solved, the reuse of the SPM solution is realized, and the SPM solution is further saved.